

Customer No.: 31561
Application No.: 10/711,512
Docket No.: 13622-US-PA

REMARKS

Present Status of the Application

The Examiner's indication allowance of claims 1-10 and claims 12-15 would be allowed if rewritten into independent form including all of the limitations of the base claim and any intervening claims is noted with great appreciation. Applicants have compliantly added the limitation "high density plasma chemical vapor deposition process" recited in claims 15 in claim 11. Therefore, claims 1-14 remain pending in the present application and patently define over prior art of record.

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CONCLUSION

It is believed that all the pending claims 1-14 of the present application patently define over the prior art and are in proper condition for allowance. If the Examiner believes that a telephone conference would expedite the examination of the above-identified patent application, the Examiner is invited to call the undersigned.

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Respectfully submitted,

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